

## PATENT ABSTRACTS OF JAPAN

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TAGUCHI SATOSHI**(54) METHOD FOR REFINING AQUEOUS HYDROGEN PEROXIDE****(57)Abstract:**

**PURPOSE:** To provide aq. hydrogen peroxide having high purity which has extremely low concn. of a metal content as an impurity, and thereby, which is suitable to be used for the production process of semiconductors.

**CONSTITUTION:** In this method, aq. crude hydrogen peroxide containing metal contents as an impurity is subjected to contact treatment with a strong-acidic cation exchange resin to obtain the objective high-purity aq. hydrogen peroxide. In this method, the strong-acidic cation exchange resin pre-treated by being made in contact with the aq. hydrogen peroxide having  $\leq 20$ wt.ppt concn. of each metal component.

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